

Figure 1

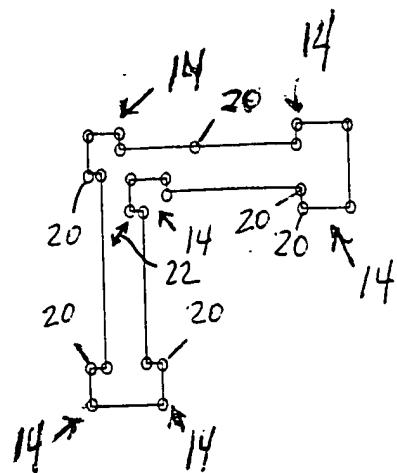


Figure 2

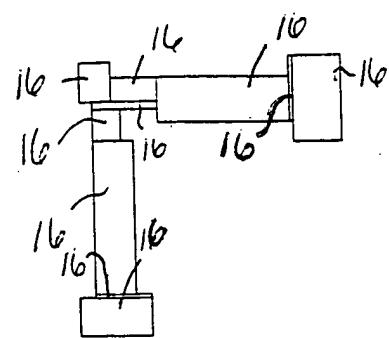


Figure 3

revising a polygon based on mask CD distributions to provide a virtual mask, such as by statistically varying layouts which have passed through an OPC procedure (for example, by moving corners of a polygon and/or by re-sizing primitives, based on mask CD distribution)

obtaining statistical parameters based on the virtual mask imaging (such as by simulating an aerial and/or latent image, calculating response functions, collecting measurements, calculating statistical parameters, and comparing the statistical parameters with design rule requirements)

Figure 4

means for revising a polygon based on mask CD distributions to provide a virtual mask, such as by statistically varying layouts which have passed through an OPC procedure (for example, by moving fragments of a polygon and/or by re-sizing primitives, based on mask CD distribution)



means for obtaining statistical parameters based on the virtual mask imaging (such as by simulating an aerial and/or latent image, calculating response functions, collecting measurements, calculating statistical parameters, and comparing the statistical parameters with design rule requirements)

Figure 5